Pilot Scale Remediation of Dissolved Vinyl Chloride Plume Using *In Situ* Chemical Oxidation IR Site 5 – NAS North Island

U.S. EPA TECHNICAL SUPPORT PROJECT SEMI-ANNUAL MEETING

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Roadmap of This Presentation

- Background
- In Situ Chemical Oxidation Using Fenton's Reaction
 - What, How, and Why
 - In Situ Chemical Oxidation Vendors
- Pilot Scale Remediation at IR Site 5
 - Operation and Results
- Conclusions
- Points of Contact





Background

Former Hazardous Waste Pits (1940s to 1965)

Site Geology and Hydrogeology

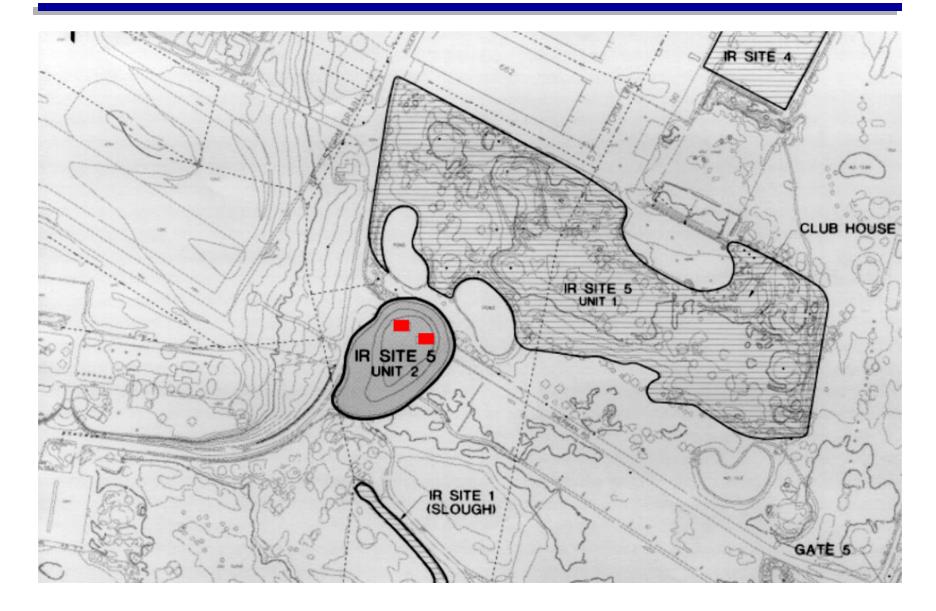
- Spanish Bight Embayment (dredged fill)
 - 1. Hydraulic Fill Fine to medium sand and silty sand
 - 2. Bayfloor Sediments Soft, finer-grained sediments approx.
 10 ft bgs defines the bottom of the contaminated aquifer
 - 3. Bay Point Formation Poorly consolidated sand unit that constitutes formational material that outcrops at NASNI
- Shallow groundwater (5 ft. bgs)

MNA is working via reductive dechlorination

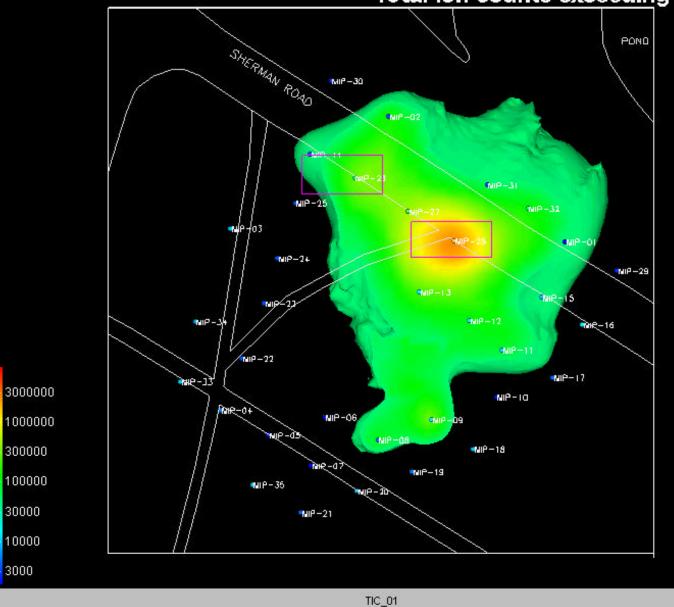
- VOC plume may reach slough
- TCRA objective
 - Reduce the mass of VOCs in the soil and groundwater



IR Site 5 VOC Groundwater Plume



SCAPS MIP Assessment of VOC Impacted Soil & GW



counts

Fotal ion

Total ion counts exceeding 50000

In Situ Oxidation Using Fenton's Reagent

Fenton's Reagent: Iron + Hydrogen Peroxide

- Powerful oxidation technology used by the waste water industry to treat organic wastes
- $\blacksquare H_2O_2 + Fe^{+2} \ddot{U}Fe^{+3} + OH^- + OH^-$
- Produces hydroxyl radicals (OH•)
- Typically requires acidified pH (acid injection)



Exothermic (heat producing) reaction

Why In-situ Chemical Oxidation?

Powerful In-situ technology

- Complete of contaminants to CO₂ and H₂O
- Cost Effective
- Rapid Treatment
 - Weeks to Months
- Eliminates Waste Generation and Transportation
- Minimal Site Disruption



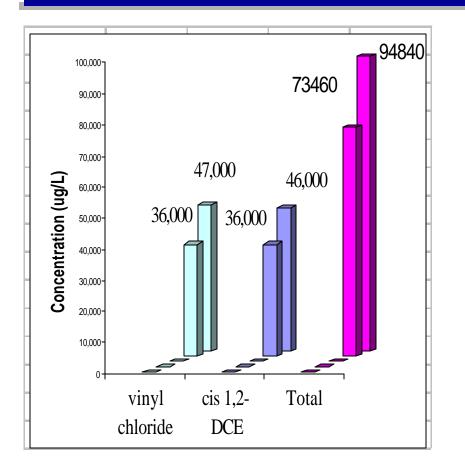
Fenton's Reagent Vendors

Each has a unique delivery/injection scheme

- Patented processes
- Vendors include:
 - Clean OX, ManTech Environmental Corp.
 - ISOTEC
 - Geo Cleanse
 - On-Contact, EBS



Bench Test

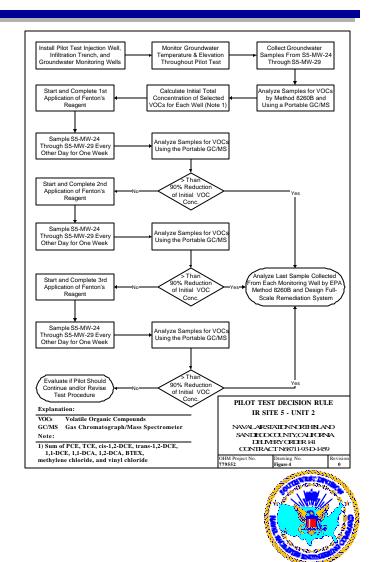


- Utilized soil and groundwater samples collected at the site
- Three tests performed
- Achieved 99.99% to 100% concentration reduction of the target VOCs
- Test results confirm in-situ chemical oxidation is a viable technology

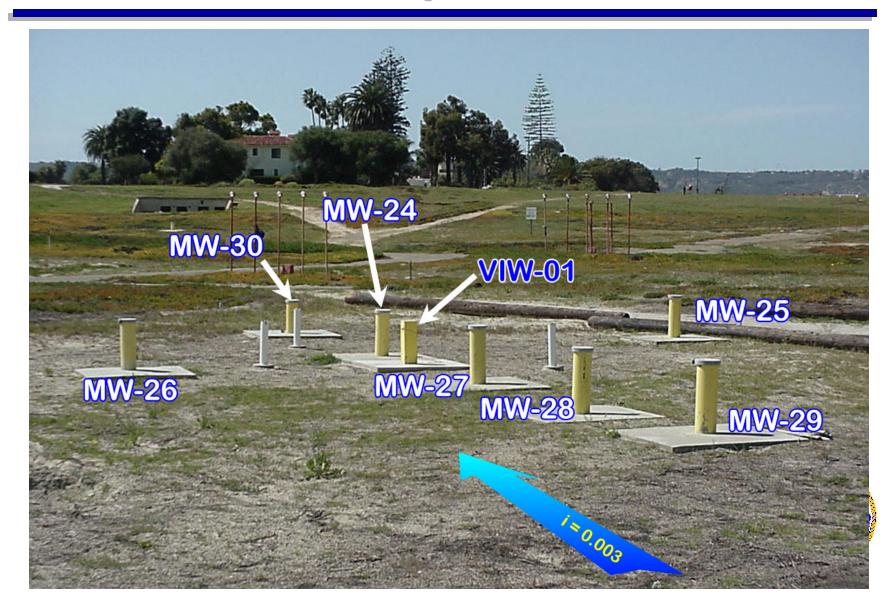


Pilot Test Objectives

- Confirm that in situ chemical oxidation is capable of achieving the cleanup objectives
- Develop full-scale design parameters (rate of contaminant reduction, well spacing)
- Develop preliminary operational parameters (chemical concentrations and injection rates)
- Exit Strategy



Pilot Test Well Array



Injection Well





Injection Wellhead



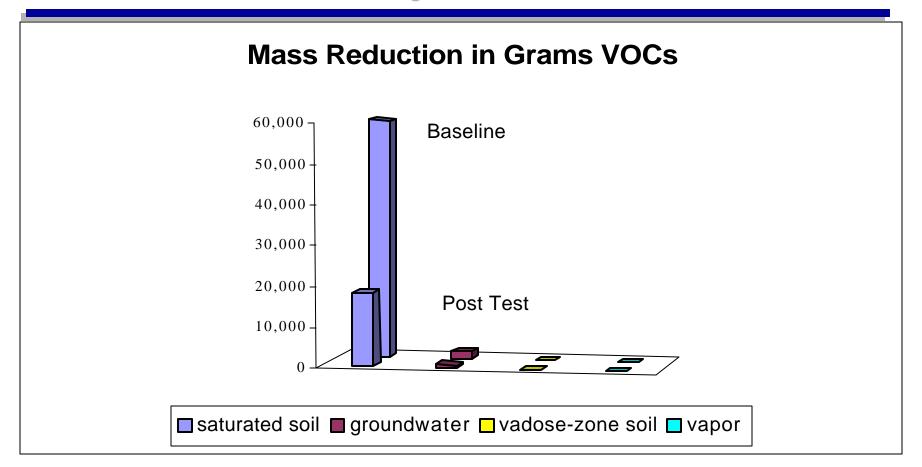


Test Results — Summary

- Effect of injection seen at full 30-ft radius in monitoring and sampling data
- VOC GW concentrations reduced by ~ 50% to ~ 90%
- VOC mass reduction of ~ 50% throughout 25-ft treatment radius
 - ~ 70% mass reduction in saturated soil
- Viable technology for full scale source removal treatment



Mass Reduction by Phase

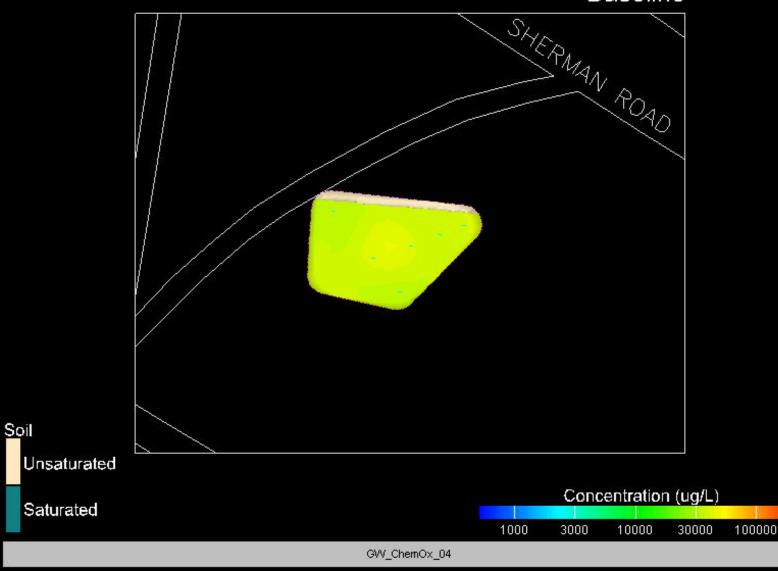




Pilot Test Groundwater Results

Total VOCs in Groundwater Concentration exceeding 500 ug/L

Baseline



Summary Pilot Test

- Mass reduction
- Technology effective for source removal
 - May not be applicable to obtain water quality objectives
- Evidence of Fenton's type reaction noted
 - Contaminant reduction not due dilution and mass transfer
- Aquifers were not adversely affected
- Reduced soil contamination at and below the water table



Current Status & Future Plans

- Regulatory review process
- Initiate full-scale remediation in Summer 2001



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